WEST Search History

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DATE: Thursday, April 22, 2004

Hide?	Set Name	Query	Hit Count
	DB=PGPB, USA	PT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=	YES; OP=ADJ
	L7	13 and (gas guard)	1
	L6	13 and (gas injection tube)	1
\mathbf{n}	L5	L3 and (gas spraying)	9
	L4	L3 and (forming water layer)	1
	L3	L1 and (water supply)	1488
	_ L2	L1 and (water supply means)	0
	L1	cleaning apparatus	28443

END OF SEARCH HISTORY

L Number	Hits	Search Text	DB	Time stamp
1	2820	(134/182,183,148,153,902).CCLS.	USPAT; US-PGPUB	2004/04/22 11:49
2	966	((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$)	USPAT; US-PGPUB	2004/04/22
3	953	and (gas spray\$) and (gas guard) (((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and	USPAT; US-PGPUB	2004/04/22 11:52
4	847	(gas injection tube) ((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer	USPAT; US-PGPUB	2004/04/22 11:53
5	806	chuck) (((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer	USPAT; US-PGPUB	2004/04/22 11:54
6	538	chuck)) and (water layer) ((((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer	USPAT; US-PGPUB	2004/04/22 11:54
7	477	chuck)) and (water layer)) and chamber (((((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer chuck)) and (water layer))	USPAT; US-PGPUB	2004/04/22 11:55
8	351	and chamber) and (single type) (((((((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer chuck)) and (water layer)) and chamber) and (single type)) and (x-y	USPAT; US-PGPUB	2004/04/22 11:55
11	0,	drive mechanism) ((((((((((((((((((((((((((((((((((((USPAT; US-PGPUB	2004/04/22 11:59
10	2	and holes) and (megasonic transducer) (((((((((((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer chuck)) and (water layer)) and chamber) and (single type)) and (x-y drive mechanism)) and (frustoconical)) and holes	USPAT; US-PGPUB	2004/04/22 11:59
9	7	and notes ((((((((((((((((((((((((((((((((((((USPAT; US-PGPUB	2004/04/22 12:17
12	81	1	USPAT; US-PGPUB	2004/04/22 12:18

				1
13.	81	((((((((((((134/182,183,148,153,902).CCLS.)	USPAT;	2004/04/22
		and (cleaning apparatus) and (water	US-PGPUB	12:18
		supply\$) and (gas spray\$) and (gas		
		guard)) and (gas injection tube)) and		
		(rotary wafer chuck)) and (water layer))		
		and chamber) and (single type)) and (x-y		* -
		drive mechanism)) and megasonic) and		
		(cleaning gas)	USPAT;	2004/04/22
-	0	(136/6).CCLS.	US-PGPUB	11:48
İ	1132	(134/6).CCLS.	USPAT;	2003/10/28
_	1132	(134/6).0013.	US-PGPUB	13:36
_	266	134/1.ccls. and (electrostatic charge)	USPAT;	2003/10/28
	200	134/1.ccis. and (electrostatic charge)	US-PGPUB	13:38
_	191	(134/1.ccls. and (electrostatic charge))	USPAT;	2003/10/28
		and (semiconductor processing tool)	US-PGPUB	13:39
_	105	(156/345.35).CCLS.	USPAT;	2004/03/29
		, , ,	US-PGPUB	11:20
_	0	("llandopticsormirrororrutheniumorcollecto	PPSPATPN.	2004/03/29
			US-PGPUB	11:22
-	15	((156/345.35).CCLS.) and (optics or	USPAT;	2004/03/29
	}	mirror or collectors or ruthenium)	US-PGPUB	11:23
-	105	(134/1.1 and etchant) and energy	USPAT;	2004/03/29
			US-PGPUB	11:55
-	5	(((134/1.1 and etchant) and energy) and	USPAT;	2004/03/29
		light) and mirror	US-PGPUB	11:43
-	4	(((134/1.1 and etchant) and energy) and	USPAT;	2004/03/29
		light) and optics	US-PGPUB	11:43
_	163	134/1.1 and etchant	USPAT;	2004/03/29
			US-PGPUB	11:51
	1351	134/1.3	USPAT;	2004/03/29
		(/124/1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	US-PGPUB	11:52
-	46	((134/1.1 and etchant) and energy) and	USPAT; US-PGPUB	11:56
	1,000	light	USPAT;	2004/03/29
-	1663	134/21	US-PGPUB	11:56
	39	134/21 and ionizing	USPAT;	2004/03/29
_	39	134/21 and lonizing	US-PGPUB	14:18
	619653	lithograph chamber	USPAT;	2004/03/29
	013033	Treffograph chamber	US-PGPUB	14:19
_	646813	lithography chamber	USPAT;	2004/03/29
•	0.0023	110110g1upiij siianast	US-PGPUB	14:19
l <u>-</u>	377610	(lithography chamber) and (optical	USPAT;	2004/03/29
		component)	US-PGPUB	14:20
_	44457	((lithography chamber) and (optical	USPAT;	2004/03/29
	1	component)) and etching	US-PGPUB	14:21
_	43483	(((lithography chamber) and (optical	USPAT;	2004/03/29
	1	component)) and etching) and (first	US-PGPUB	14:21
		chamber)		
-	8255	((((lithography chamber) and (optical	USPAT;	2004/03/29
1		component)) and etching) and (first	US-PGPUB	14:22
1		chamber)) and mirror		
-	8054	(((((lithography chamber) and (optical	USPAT;	2004/03/29
		component)) and etching) and (first	US-PGPUB	14:23
i		chamber)) and mirror) and (first etchant)	110222	2004/03/30
-	7703	((((((lithography chamber) and (optical	USPAT;	2004/03/29
		component)) and etching) and (first	US-PGPUB	14:23
		chamber)) and mirror) and (first etchant)) and (light source)		j
	1040	<pre> etchant)) and (light source) ((((((lithography chamber) and (optical))</pre>	USPAT;	2004/03/29
-	1040	component)) and etching) and (first	US-PGPUB	14:24
		chamber)) and mirror) and (first	ON FGEOD	1 1, 2,
		etchant)) and (light source)) and ioniz\$		
	317	(((((((lithography chamber) and (optical	USPAT;	2004/03/29
	31/	component) and etching and (first	US-PGPUB	14:24
		chamber)) and mirror) and (first	15 15100	
		etchant)) and (light source)) and ioniz\$)		
	1	and (incidence collectors)		
L	1	,,	·	

-	185	(((((((((lithography chamber) and	USPAT;	2004/03/29
· .		(optical component)) and etching) and (first chamber)) and mirror) and (first etchant)) and (light source)) and ioniz\$) and (incidence collectors)) and cleaning ((((((((((lithography chamber) and (optical component)) and etching) and (first chamber)) and mirror) and (first etchant)) and (light source)) and ioniz\$) and (incidence collectors)) and cleaning) and 156/\$.ccls.	US-PGPUB USPAT; US-PGPUB	14:25 2004/03/29 14:26

L Number	Hits	Search Text	DB	Time stamp
1	2820	(134/182,183,148,153,902).CCLS.	USPAT; US-PGPUB	2004/04/22
2	966	((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas guard)	USPAT; US-PGPUB	2004/04/22 11:51
3	953	(((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)	USPAT; US-PGPUB	2004/04/22 11:52
4	847	((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer chuck)	USPAT; US-PGPUB	2004/04/22 11:53
5	806	(((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer chuck)) and (water layer)	USPAT; US-PGPUB	2004/04/22 11:54
6	538	<pre>chuck) and (water layer) ((((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer chuck)) and (water layer)) and chamber</pre>	USPAT; US-PGPUB	2004/04/22 11:54
7	477	<pre>((((((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer chuck)) and (water layer))</pre>	USPAT; US-PGPUB	2004/04/22 11:55
8	351	and chamber) and (single type) (((((((((((134/182,183,148,153,902).CCLS.) and (cleaning apparatus) and (water supply\$) and (gas spray\$) and (gas guard)) and (gas injection tube)) and (rotary wafer chuck)) and (water layer)) and chamber) and (single type)) and (x-y	USPAT; US-PGPUB	2004/04/22 11:55
11	0	drive mechanism) ((((((((((((((((((((((((((((((((((((USPAT; US-PGPUB	2004/04/22 11:59
10	2	and holes) and (megasonic transducer) ((((((((((((((((((((((((((((((((((((USPAT; US-PGPUB	2004/04/22 11:59
9	7	<pre>((((((((((((((((((((((((((((((((((((</pre>	USPAT; US-PGPUB	2004/04/22 12:17
12	81	<pre>((((((((((((((((((((((((((((((((((((</pre>	USPAT; US-PGPUB	2004/04/22

13	81	((((((((((((((((((((((((((((((((((((((USPAT;	2004/04/22
		and (cleaning apparatus) and (water	US-PGPUB	13:52
	-	supply\$) and (gas spray\$) and (gas		
		guard)) and (gas injection tube)) and	1	
		(rotary wafer chuck)) and (water layer))		
		and chamber) and (single type)) and (x-y	į	
		drive mechanism)) and megasonic) and		
		(cleaning gas)		
15	0	("14andgasspraying").PN.	USPAT;	2004/04/22
			US-PGPUB	13:54
16	. 0	("14andgasspraying").PN.	USPAT;	2004/04/22
		•	US-PGPUB	13:54
14	1532	(134/902).CCLS.	USPAT;	2004/04/22
			US-PGPUB	14:36
17	753	(134/153).CCLS.	USPAT;	2004/04/22
			US-PGPUB	14:37